

L Number	Hits	Search Text	DB	Time stamp
1	2560	dither\$5 and detect\$5 and beam	USPAT; EPO; JPO; DERWENT	2004/02/05 11:14
2	1601	(dither\$5 and detect\$5 and beam) and pattern	USPAT; EPO; JPO; DERWENT	2004/02/05 11:14
3	668	(dither\$5 and detect\$5 and beam) and (pattern grid) same dither\$5	USPAT; EPO; JPO; DERWENT	2004/02/05 11:14
4	374	((dither\$5 and detect\$5 and beam) and (pattern grid) same dither\$5) and shap\$5	USPAT; EPO; JPO; DERWENT	2004/02/05 11:19
5	42	((dither\$5 and detect\$5 and beam) and (pattern grid) same dither\$5) and 250/\$.ccls.	USPAT; EPO; JPO; DERWENT	2004/02/05 11:16
6	40	((dither\$5 and detect\$5 and beam) and (pattern grid) same dither\$5) and dither\$5.ti.	USPAT; EPO; JPO; DERWENT	2004/02/05 11:17
7	2	((dither\$5 and detect\$5 and beam) and (pattern grid) same dither\$5) and dither\$5.ti.) and 250/\$.ccls.	USPAT; EPO; JPO; DERWENT	2004/02/05 11:17
8	32	((dither\$5 and detect\$5 and beam) and (pattern grid) same dither\$5) and shap\$5) and shadow\$5	USPAT; EPO; JPO; DERWENT	2004/02/05 11:19
9	57	((dither\$5 and detect\$5 and beam) and (pattern grid) same dither\$5) and shadow\$5	USPAT; EPO; JPO; DERWENT	2004/02/05 11:19
-	124	250/49\$.ccls. and shaping adj aperture	USPAT; EPO; JPO; DERWENT	2004/02/05 11:13
-	19	(250/49\$.ccls. and shaping adj aperture ) and raster	USPAT; EPO; JPO; DERWENT	2002/11/05 08:03
-	9	250/49\$.ccls. and shaping adj aperture and mesh	USPAT; EPO; JPO; DERWENT	2002/11/05 09:11
-	4	250/49\$.ccls. and shadow adj pattern	USPAT; EPO; JPO; DERWENT	2002/11/05 09:14
-	102	(250/49\$.ccls. and shaping adj aperture ) and deflector	USPAT; EPO; JPO; DERWENT	2002/11/05 11:06
-	4609	250/492\$.ccls. and beam	USPAT; EPO; JPO; DERWENT	2002/11/05 11:15
-	934	(250/492\$.ccls. and beam) and lithography	USPAT; EPO; JPO; DERWENT	2002/11/05 12:32
-	393	(250/492\$.ccls. and beam) and lithography and particle	USPAT	2002/11/05 11:17
-	245	(250/492\$.ccls. and beam) and lithography and particle and aperture	USPAT	2002/11/05 16:02
-	52	(250/492\$.ccls. and beam) and lithography and particle and aperture and offset	USPAT	2002/11/05 14:24
-	46	(250/492\$.ccls. and beam) and lithography and mesh	USPAT; EPO; JPO; DERWENT	2002/11/05 16:39
-	1	((250/492\$.ccls. and beam) and lithography and mesh) and array with target	USPAT; EPO; JPO; DERWENT	2002/11/05 12:54
-	44	(250/492\$.ccls. and beam) and lithography and particle and aperture and angl\$6 and offset	USPAT	2002/11/05 15:50
-	12	spot adj exposure adj time	USPAT	2002/11/05 15:50
-	16	(250/492\$.ccls. and beam) and lithography and particle and aperture and fiducial	USPAT	2002/11/05 16:02

-	1	250/49\$.ccls. and shaping adj aperture and dither\$4	USPAT; EPO; JPO; DERWENT	2003/04/21 10:46
-	13	250/49\$.ccls. and dither\$4 and pattern	USPAT; EPO; JPO; DERWENT	2003/04/21 10:47
-	6	250/49\$.ccls. and dither\$4 and deflect\$4 and detect\$4	USPAT; EPO; JPO; DERWENT	2003/04/21 10:49
-	17	250/49\$.ccls. and dither\$4	USPAT; EPO; JPO; DERWENT	2003/04/21 10:48
-	167	250/49\$.ccls. and raster and deflect\$4 and detect\$4	USPAT; EPO; JPO; DERWENT	2003/04/21 10:49
-	148	250/49\$.ccls. and raster and deflect\$4 and detect\$4 and pattern	USPAT; EPO; JPO; DERWENT	2003/04/21 10:50
-	13344	dither\$6	USPAT; EPO; JPO; DERWENT	2003/10/14 16:45
-	3363	dither\$6 and beam	USPAT; EPO; JPO; DERWENT	2003/10/14 16:46
-	2038	(dither\$6 and beam ) and pattern	USPAT; EPO; JPO; DERWENT	2003/10/14 16:46
-	1557	((dither\$6 and beam ) and pattern) and detect\$6	USPAT; EPO; JPO; DERWENT	2003/10/14 16:46
-	631	((((dither\$6 and beam ) and pattern) and detect\$6) and dither\$5 same pattern	USPAT; EPO; JPO; DERWENT	2003/10/14 16:47
-	39	(((((dither\$6 and beam ) and pattern) and detect\$6) and dither\$5 same pattern) and 250/\$.ccls.	USPAT; EPO; JPO; DERWENT	2003/10/15 09:07
-	343	(((((dither\$6 and beam ) and pattern) and detect\$6) and dither\$5 same pattern) and shap\$5	USPAT; EPO; JPO; DERWENT	2003/10/14 16:48
-	14	((((((dither\$6 and beam ) and pattern) and detect\$6) and dither\$5 same pattern) and shap\$5) and aperture) and 250/\$.ccls.	USPAT; EPO; JPO; DERWENT	2003/10/14 16:48
-	111	((((((dither\$6 and beam ) and pattern) and detect\$6) and dither\$5 same pattern) and shap\$5) and aperture	USPAT; EPO; JPO; DERWENT	2003/10/15 09:13
-	0	dither and shadow adj pattern	USPAT; EPO; JPO; DERWENT	2003/10/15 08:51
-	3	dither\$4 and shadow adj pattern	USPAT; EPO; JPO; DERWENT	2003/10/15 08:51
-	15	dither and (mesh grid) and pattern and detect\$6 and 250/\$.ccls.	USPAT; EPO; JPO; DERWENT	2003/10/15 09:08
-	126	lithography and dither	USPAT; EPO; JPO; DERWENT	2003/10/15 09:13
-	25	(lithography and dither) and (mesh grid)	USPAT; EPO; JPO; DERWENT	2003/10/15 09:14
-	4	((("6614035") or ("5773836") or ("6291819") or ("6175122"))).PN.	USPAT	2003/10/15 10:00
-	0	((("6614035") or ("5773836") or ("6291819") or ("6175122"))).PN.) and dither\$5	USPAT; EPO; JPO; DERWENT	2003/10/15 10:00

L Number	Hits	Search Text	DB	Time stamp
-	3	dither\$4 and shadow adj pattern	USPAT; EPO; JPO; DERWENT	2003/04/01 16:28
-	335	dither\$4 and 250/\$.ccls.	USPAT; EPO; JPO; DERWENT	2003/04/01 16:29
-	94	(dither\$4 and 250/\$.ccls.) and deflect\$4 and detect\$4	USPAT; EPO; JPO; DERWENT	2003/04/01 16:29
-	62	((dither\$4 and 250/\$.ccls.) and deflect\$4 and detect\$4) and shap\$4	USPAT; EPO; JPO; DERWENT	2003/04/01 16:29
-	35	((((dither\$4 and 250/\$.ccls.) and deflect\$4 and detect\$4) and shap\$4) and pattern	USPAT; EPO; JPO; DERWENT	2003/04/01 16:29

L Number	Hits	Search Text	DB	Time stamp
-	124	250/49\$.ccls. and shaping adj aperture	USPAT; EPO; JPO; DERWENT	2003/04/21 10:45
-	19	(250/49\$.ccls. and shaping adj aperture ) and raster	USPAT; EPO; JPO; DERWENT	2002/11/05 08:03
-	9	250/49\$.ccls. and shaping adj aperture and mesh	USPAT; EPO; JPO; DERWENT	2002/11/05 09:11
-	4	250/49\$.ccls. and shadow adj pattern	USPAT; EPO; JPO; DERWENT	2002/11/05 09:14
-	102	(250/49\$.ccls. and shaping adj aperture ) and deflector	USPAT; EPO; JPO; DERWENT	2002/11/05 11:06
-	4609	250/492.\$ccls. and beam	USPAT; EPO; JPO; DERWENT	2002/11/05 11:15
-	934	(250/492.\$ccls. and beam) and lithography	USPAT; EPO; JPO; DERWENT	2002/11/05 12:32
-	393	(250/492.\$ccls. and beam) and lithography and particle	USPAT	2002/11/05 11:17
-	245	(250/492.\$ccls. and beam) and lithography and particle and aperture	USPAT	2002/11/05 16:02
-	52	(250/492.\$ccls. and beam) and lithography and particle and aperture and offset	USPAT	2002/11/05 14:24
-	46	(250/492.\$ccls. and beam) and lithography and mesh	USPAT; EPO; JPO; DERWENT	2002/11/05 16:39
-	1	((250/492.\$ccls. and beam) and lithography and mesh) and array with target	USPAT; EPO; JPO; DERWENT	2002/11/05 12:54
-	44	(250/492.\$ccls. and beam) and lithography and particle and aperture and angl\$6 and offset	USPAT	2002/11/05 15:50
-	12	spot adj exposure adj time	USPAT	2002/11/05 15:50
-	16	(250/492.\$ccls. and beam) and lithography and particle and aperture and fiducial	USPAT	2002/11/05 16:02
-	1	250/49\$.ccls. and shaping adj aperture and dither\$4	USPAT; EPO; JPO; DERWENT	2003/04/21 10:46
-	13	250/49\$.ccls. and dither\$4 and pattern	USPAT; EPO; JPO; DERWENT	2003/04/21 10:47
-	6	250/49\$.ccls. and dither\$4 and deflect\$4 and detect\$4	USPAT; EPO; JPO; DERWENT	2003/04/21 10:49
-	17	250/49\$.ccls. and dither\$4	USPAT; EPO; JPO; DERWENT	2003/04/21 10:48
-	167	250/49\$.ccls. and raster and deflect\$4 and detect\$4	USPAT; EPO; JPO; DERWENT	2003/04/21 10:49
-	148	250/49\$.ccls. and raster and deflect\$4 and detect\$4 and pattern	USPAT; EPO; JPO; DERWENT	2003/04/21 10:50